

ABSTRACT OF THE DISCLOSURE

An exposure apparatus includes a first exposure device for illuminating a predetermined mask with light of a predetermined wavelength under a first illumination condition, to print a first pattern on a predetermined exposure region, and a second exposure device for illuminating the mask with light of the predetermined wavelength under a second illumination condition, different from the first illumination condition, to print a second pattern on the predetermined exposure region, in which the mask has a desired pattern and an auxiliary pattern having a shape different from that of the desired pattern, and a first exposure by the first exposure device and a second exposure by the second exposure device are carried out prior to a development process.